AMENDMENT TRANSMITTAL LETTER (Large Entity)  Applicant(s): In-Sung KIM et al.							Docket No. SEC.747		
			g Date t 18, 2000		Examiner D. Collins		Group Art Unit 2823		
THE SAME	10V 1 4 ;	2001	CE HAVING SEL	F-ALIGNED	CONTACT	AND MET	HOD (	OF FABRICATING	
Transmitted herewith is an amendment in the above-identified application.  The fee has been calculated and is transmitted as shown below.									
CLAIMS AS AMENDED									
		REMAINING  AMENDMENT	HIGHEST #		R EXTRA	RATE		ADDITIONAL FEE	
TOTAL CLAIMS	20	-	20 =		0	x \$18	.00	\$0.00	
INDEP. CLAIMS 3		-	3 =	:	0	x \$84	.00	\$0.00	
Multiple Dependent Claims (check if applicable)  \$0.00									
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT \$(								\$0.00	
Please chat A duplicate A check in Mark The Communic A duplicate Mark Any a	arge De e copy o the am nissione ation or e copy o dditiona	r is hereby aut credit any ove of this sheet is o al filing fees rec	No. enclosed. to cover the horized to charge rpayment to Depo	.F.R. 1.16. 37 CFR 1.17	nclosed. ne following lo. <b>50-023</b>	8	ciated	with this	
ANDREW J. TEL REG. NO. 33,581 VOLENTINE FR. 12200 SUNRISE V RESTON, VA 20	ESZ, JF ANCOS /ALLEY	, P.L.L.C. 7 DRIVE, SUIT	) C . CE 150	Dated: N	on first class ma	t this docun	with 1 7.F.R. 1.	d fee is being deposited the U.S. Postal Service as .8 and is addressed to the atents, Washington, D.C.	
TEL. NO.: (703) 715-0870  Signature of								ng Correspondence	

cc:

Typed or Printed Name of Person Mailing Correspondence



FECTAR LILY CENTER 2800

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE,

In re PATENT APPLICATION of

In-Sung Kim et al.

Group Art Unit: 2823

Serial No.: 09/640,754

Examiner: Collins, D

Filed: August 18, 2000

or: SEMICONDUCTOR DEVICE HAVING SELF-ALIGNED CONTACT AND

METHOD OF FABRICATING THE SAME

## AMENDMENT AND REQUEST FOR RECONSIDERATION UNDER 37 C.F.R. §1.111

Honorable Commissioner of Patents and Trademarks, Washington, D.C. 20231

Sir:

November 14, 2001

In response to the Office Action of August 15, 2001, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

## In the Abstract:

Please cancel the Abstract and replace with the Abstract attached herewith.

## In the Specification:

Please rewrite the paragraph on page 2, lines 7-12, to read as follows:

When the contact plug 16, which is an underlying film pattern, and the conductive line 18, which is an overlying film pattern, are not accurately aligned, the